ABSTRACT

Provided are a purification method and purification apparatus for an alkaline treatment liquid for a semiconductor substrate, which use adsorption purification means that can purify various alkaline treatment liquids to be used for treating semiconductor substrates for various purposes so as to have an ultrahigh purity, in particular, an Fe concentration in a ppq region, and that is excellent in chemical resistance and mechanical strength. The adsorption purification means is purification means for an alkaline treatment liquid for treating a semiconductor substrate for various purposes at the time of producing, for example, a semiconductor substrate or a semiconductor device. In the purification method and purification apparatus for an alkaline treatment liquid for a semiconductor substrate, an alkaline treatment liquid is brought into contact with silicon carbide crystal surfaces in the absorption purification means, for example, an alkaline treatment liquid is allowed to flow through a gap between adsorbing plate laminates (2) whose both surfaces are CVD silicon carbide surfaces, thereby removing metal impurities contained in the alkaline treatment liquid through adsorption of the metal impurities to the silicon carbide crystal surfaces.